MAR 3 0 2005 FORM PTO-1449/A and B (Modified Francus APPLICATION NO.: 09/748,053 ATTY. DOCKET NO.: E0295.70155US00 FILING DATE: December 22, 2000 **CONFIRMATION NO.: 4482** INFORMATION DISCLOSURE Steven M. Blumenau et al. STATEMENT BY APPLICANT APPLICANT: GROUP ART UNIT: 2134 **EXAMINER:** Ho, Thomas M. Sheet 1 of 1

FOREIGN PATENT DOCUMENTS

Examiner's Initials	Cite No.	Foreign Patent Document			Name of Patentee or Applicant of Cited	Date of Publication of Tran	Translation
		Office/ Country	Number	Kind Code	(not necessary) Cited Do	Cited Document MM-DD-YYYY	(Y/N)
711		WO	99/13448	A2	SUN MICROSYSTEMS, INC.	03-18-1999	

EXAMINER:	DATE CONSIDERED:
Thomas Kor	5/21/05

#EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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